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# ELECTROPHYSICAL PROPERTIES OF $\text{Cd}_{0.96}\text{Mn}_{0.04}\text{Te}_{0.96}\text{Se}_{0.04}$ CRYSTALS AND SURFACE-BARRIER DIODES



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## ABSTRACT

$\text{Cd}_{0.96}\text{Mn}_{0.04}\text{Te}_{0.96}\text{Se}_{0.04}$  (CMTS) single crystals of p-type conductivity, grown by the Bridgman method in a 3-zone furnace with a rate of 3 mm/hour, were studied. Differential Thermal Analysis (DTA) for this alloy was performed with heating/cooling rates equal to 5 K/min with an intermediate melt dwell time of 30 min. Using the DTA method, the temperatures of the solid-liquid phase transition of  $\text{Cd}_{0.96}\text{Mn}_{0.04}\text{Te}_{0.96}\text{Se}_{0.04}$  alloys and the melting/solidification rates were determined. From the temperature dependence of the Au/CMTS/Au structure with two ohmic contacts, the resistivity of the semiconductor material was determined, which is equal to  $\rho \approx 4 \times 10^2 \Omega\text{-cm}$  at  $T = 293 \text{ K}$ . The activation energy of the dark conductivity, found from the dependence of the resistivity  $\rho$  on temperature, is equal to  $\Delta E \approx 0.24 \text{ eV}$ . Using optical measurements of the absorption coefficient from the energy of photons in the region of large  $\alpha$ , the band gap was found to be equal  $E_g = 1.495 \text{ eV}$ . Al/CMTS/Au diode structures, fabricated by vacuum deposition of Al on the p-CMTS single crystal surface, were also investigated. A quantitative interpretation of the electrical characteristics of the diodes has been done within the framework of the Saah-Noys-Shockley carrier generation-recombination model.

Key words:  $\text{Cd}_{0.96}\text{Mn}_{0.04}\text{Te}_{0.96}\text{Se}_{0.04}$  single crystals, ohmic contact, rectifying contact, generation-recombination currents.

### The band gap of CMTS single crystals

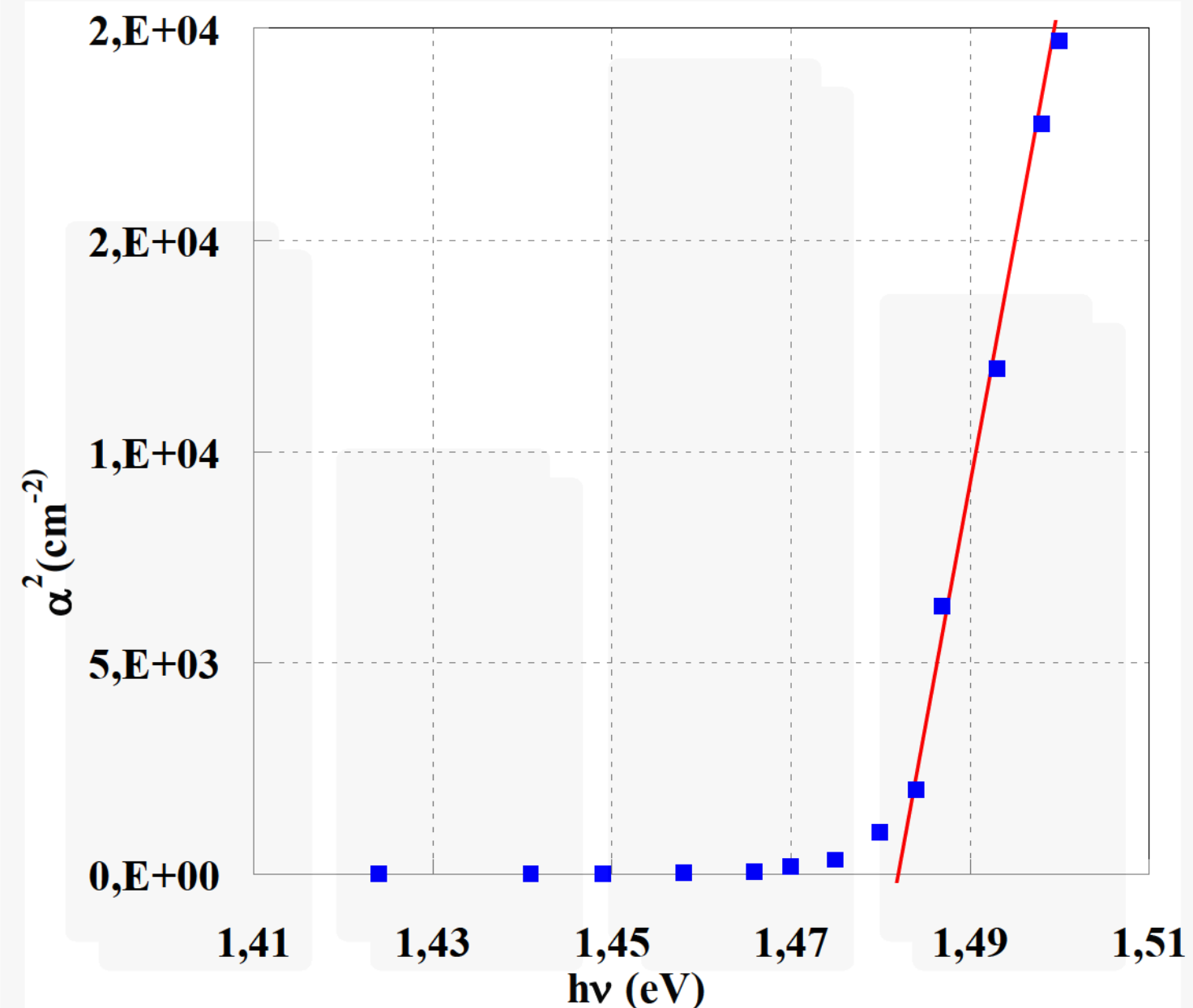


Fig. 1. Optical absorption of a single crystal with a thickness of  $d_3 \approx 0.05 \text{ mm}$  in the region of high absorption coefficients at 300 K (filled circles). The solid line is the extrapolation of the linear section to the intersection with the abscissa axis.

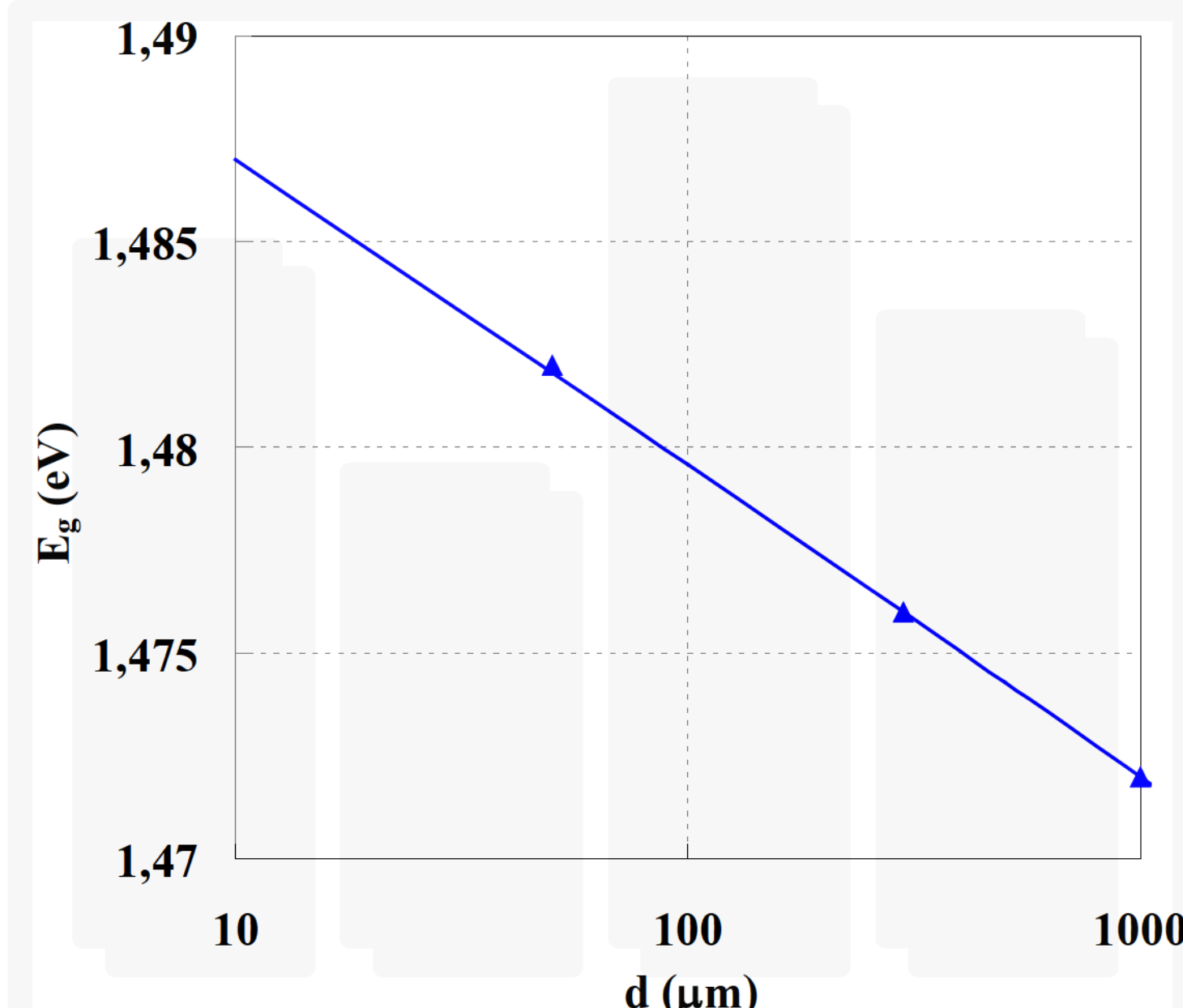


Fig. 2. Dependence of  $E_g$  on the thickness of CMTS crystals, determined from the absorption spectra in the region of large values of  $\alpha$ . The solid line approximates the dependence  $E_g = 1.495 - 0.0037 \ln d$ , cutting off on the abscissa axis at  $d = 1 \mu\text{m}$ , the desired value  $E_g = 1.495 \text{ eV}$ .

### I-V curve of an Al/CMTS/Au diode

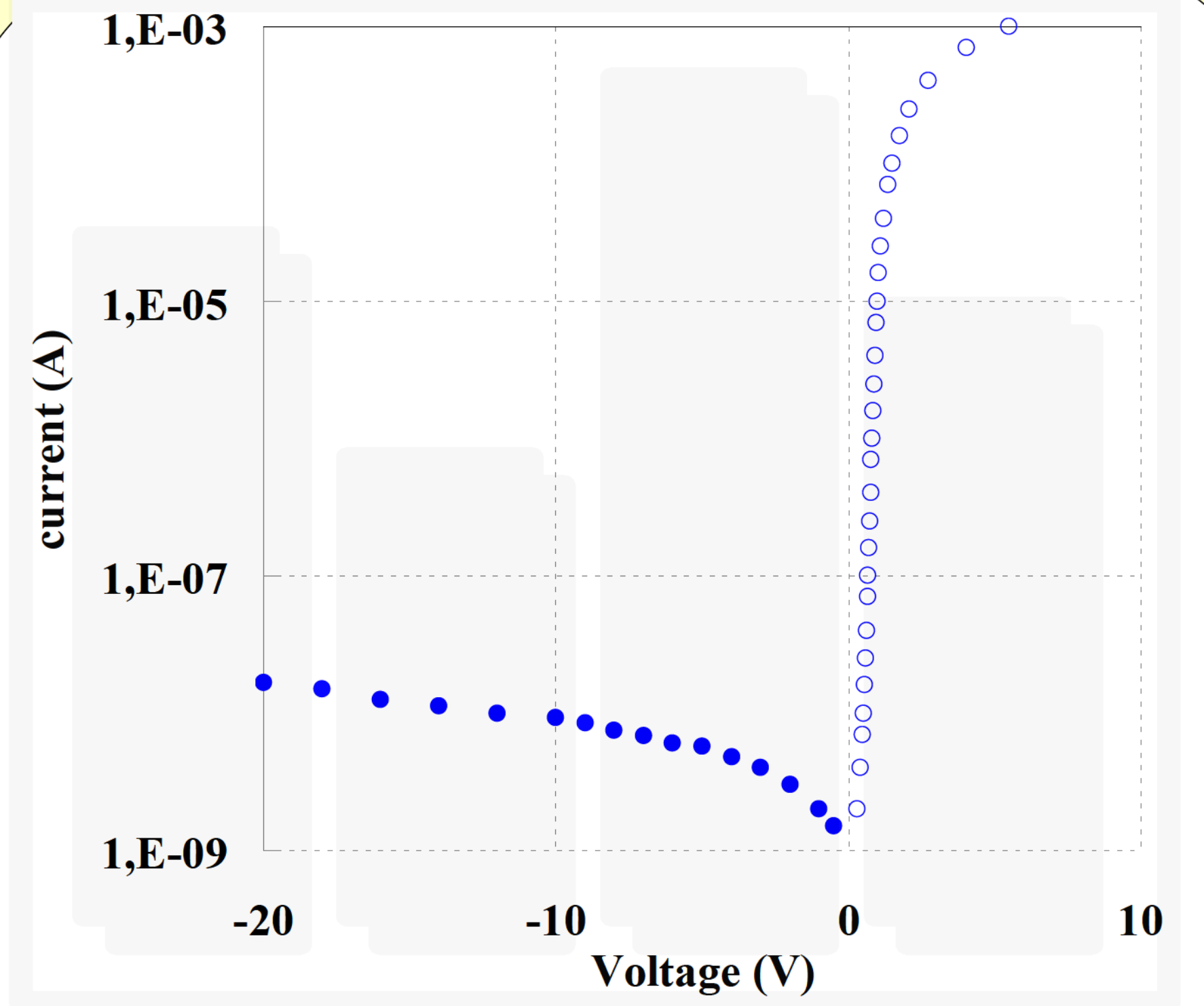


Fig. 3. I-V curve of an Al/CMTS/Au diode at 293 K.

### Temperature dependences of the resistivity for Au/CMTS/Au diodes

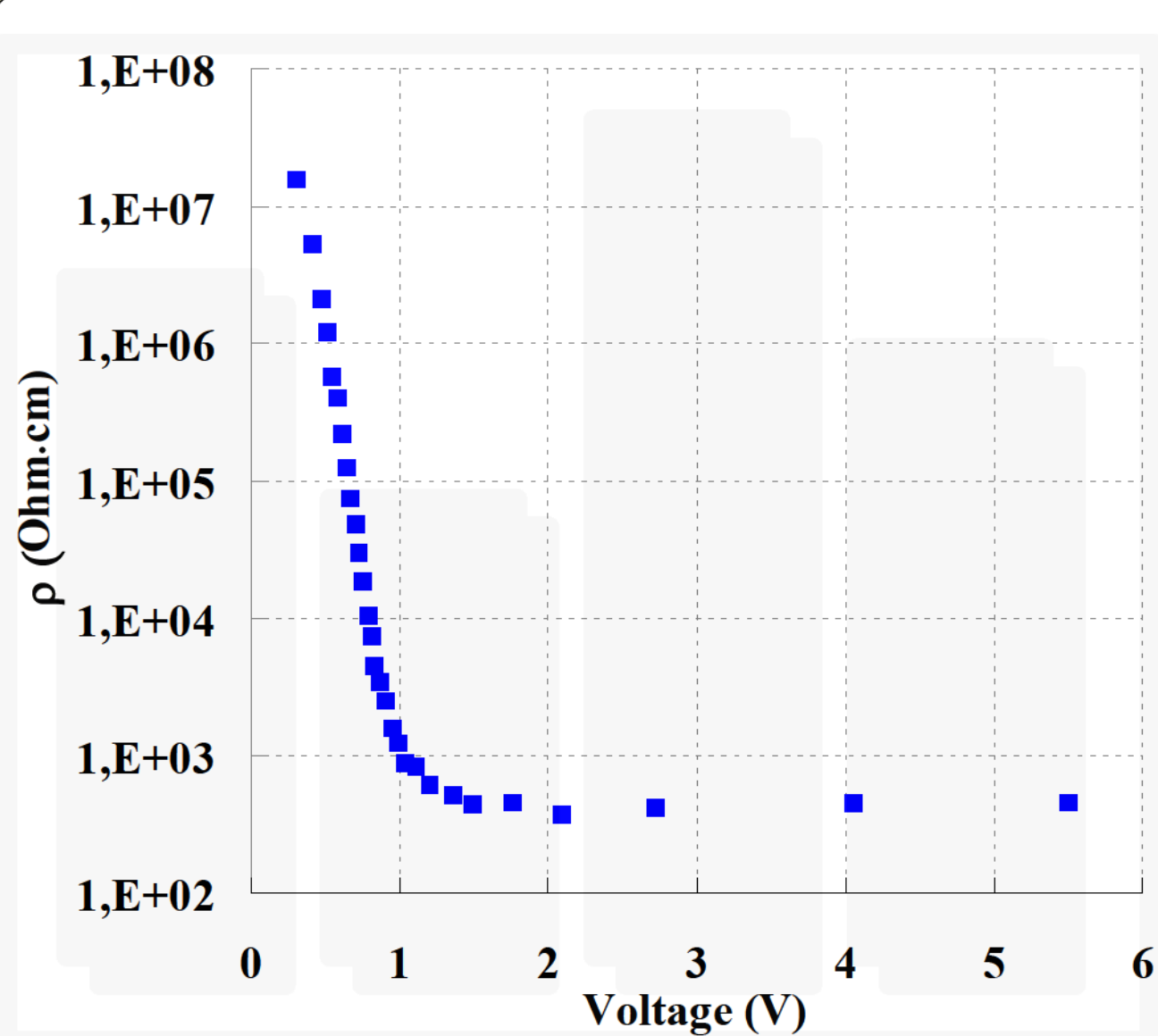


Fig. 4. The dependence of the differential resistance vs. the voltage at forward bias for the Al/CMTS/Au structure at  $T = 293 \text{ K}$ .

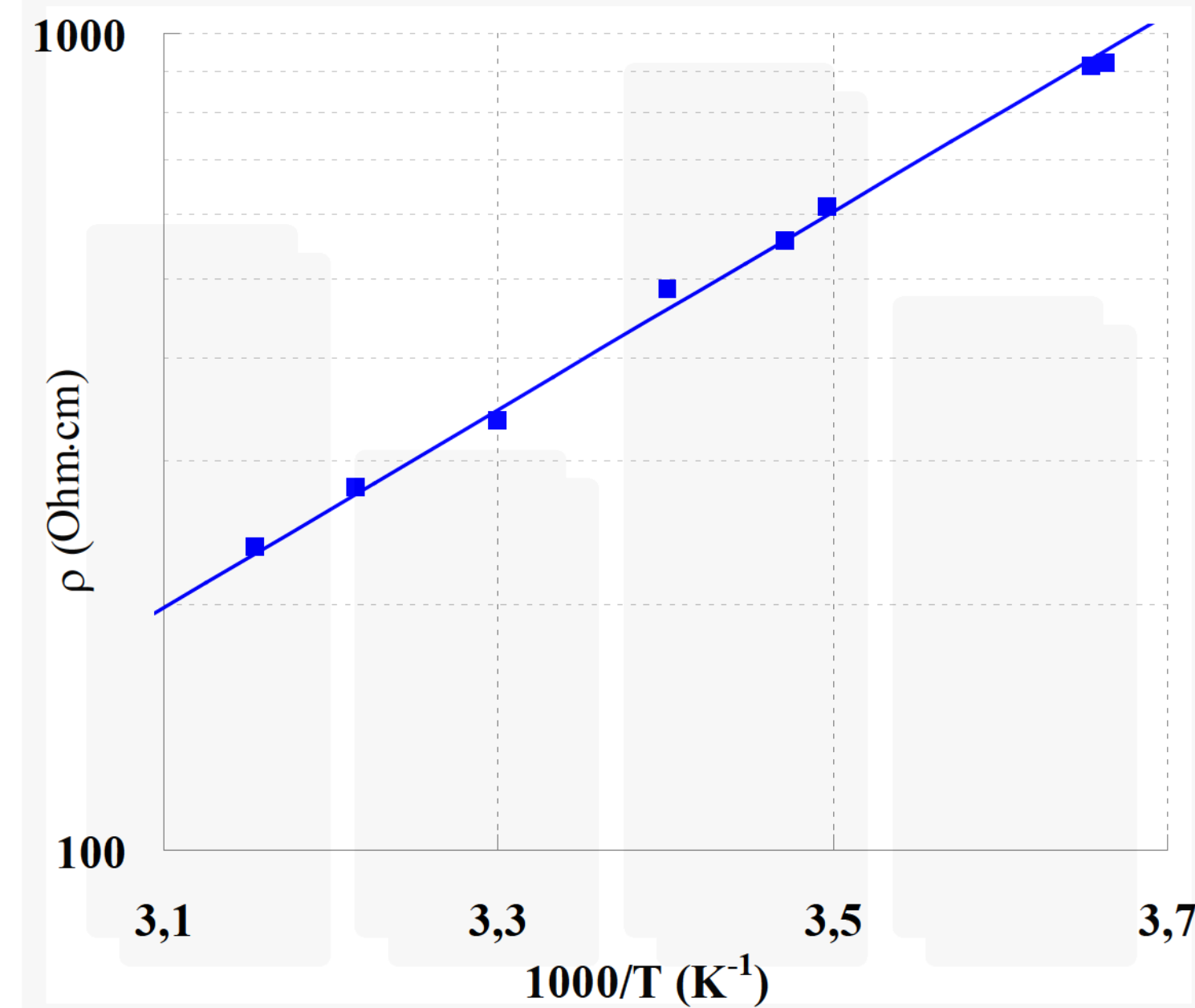


Fig. 5. The electrical resistivity of Au/CMTS/Au vs. temperature.  $\rho \approx 4 \cdot 10^2 \text{ Ohm} \times \text{cm}$  at  $T = 293 \text{ K}$ . Activation energy is  $\Delta E \approx 0.24 \text{ eV}$ .

### I-V curve of Al/CMTS/Au diode

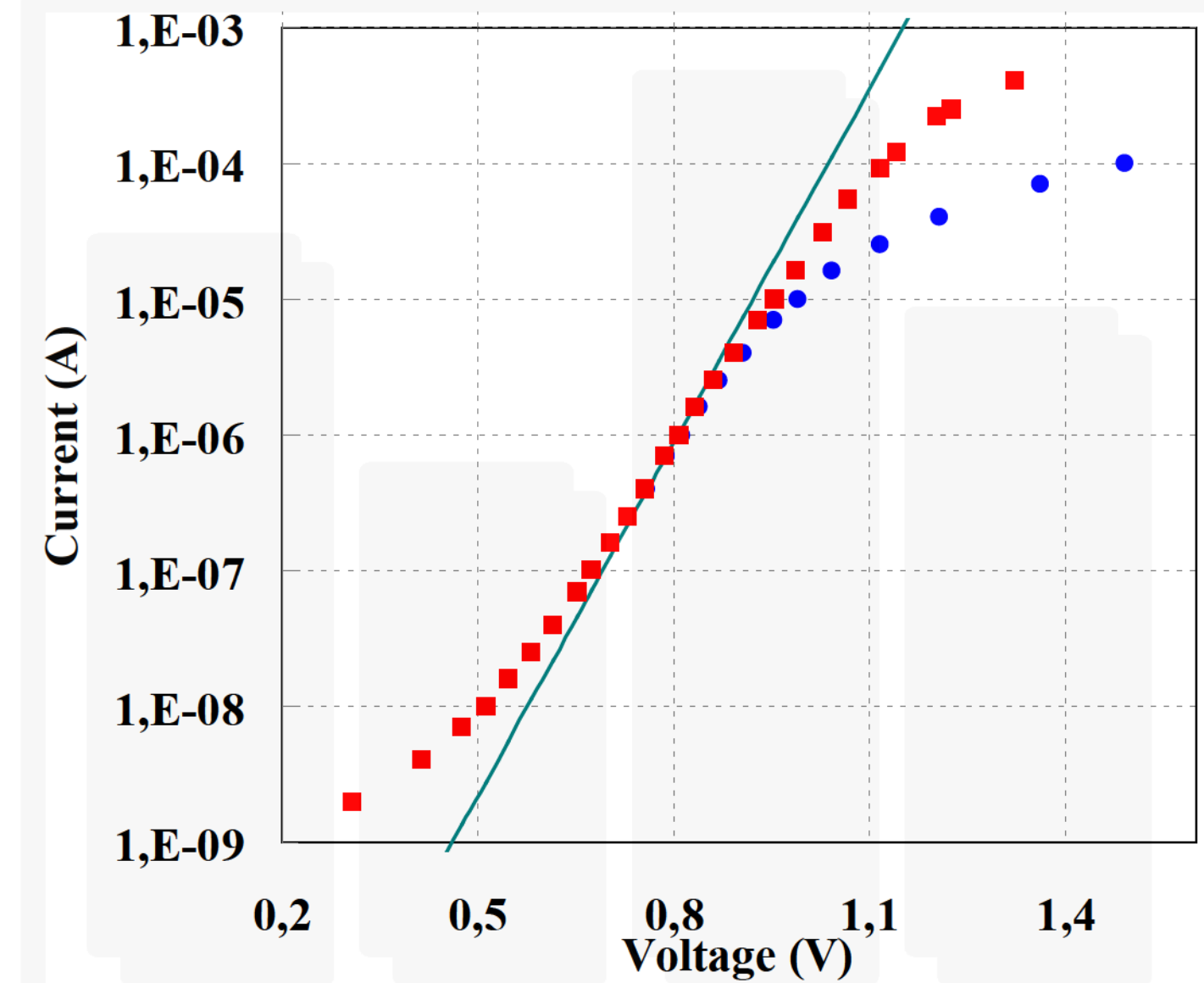


Fig. 6. I-V curve of a Al/CMTS/Au diode at forward bias. Filled circles - without taking into account the voltage drop across the series resistance of the crystal, empty circles - taking it into account. Solid straight line - theoretical dependence  $I \sim \exp(eU/2kT)$ .  $T = 293 \text{ K}$ .

### Comparison of the calculated I-V curve with the experiment for the Al/CMTS/Au diode

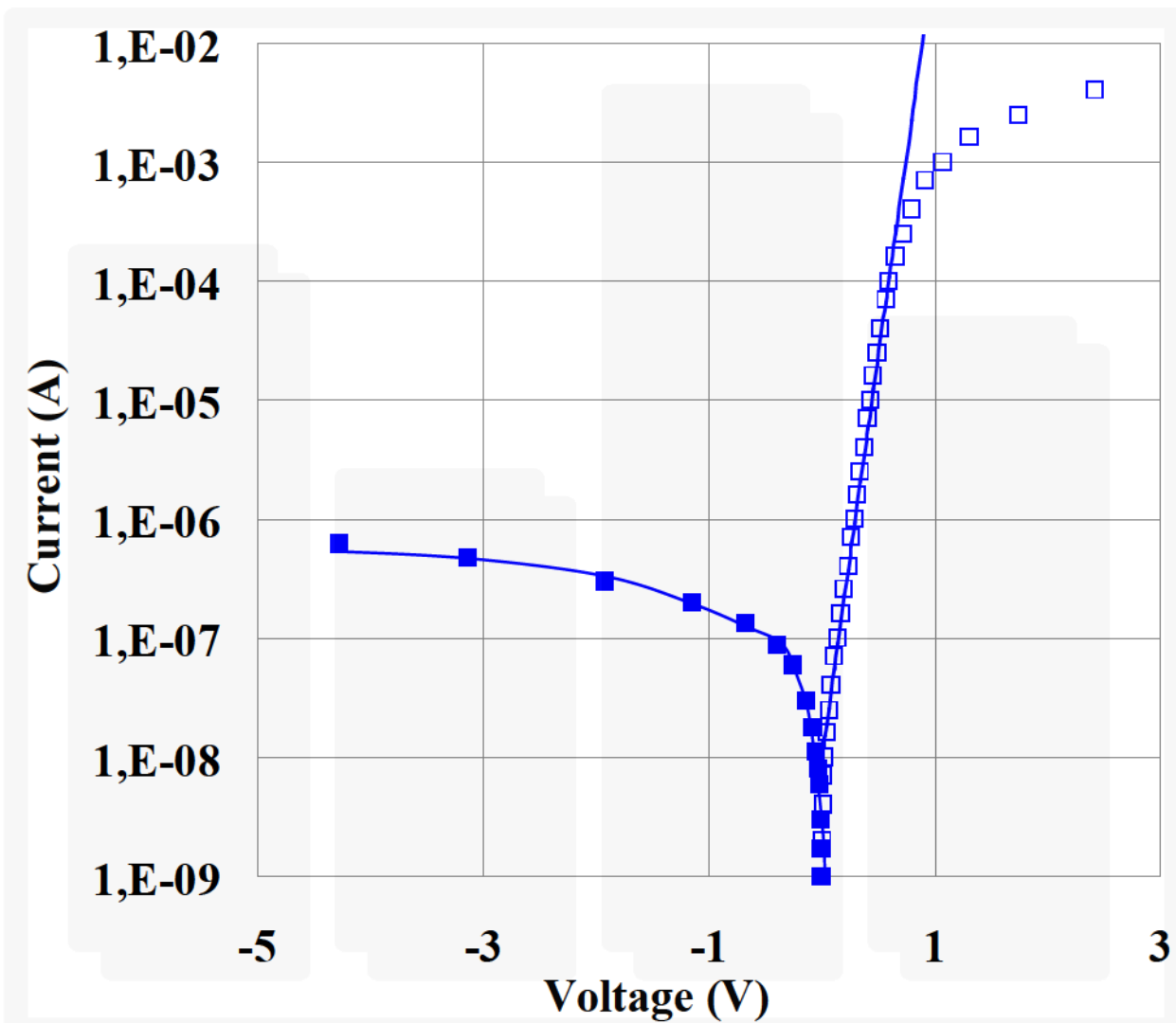


Fig. 5. Experimental I-V curve of the Al/CMTS/Au diode. Filled squares - reverse bias, open squares - forward bias. The solid line is the result of calculations.

$$v(x, U) = \frac{n(x, U)p(x, U) - n_i^2}{\tau_{po}[n(x, U) + n_i] + \tau_{no}[p(x, U) + p_i]} \quad (1) \quad p_i = \frac{N_v}{\exp\left(\frac{E_g - E_t}{kT}\right) + 1} \quad (2)$$

$$n_i = \frac{N_c}{\exp\left(\frac{E_t}{kT}\right) + 1} \quad (3) \quad n(x, U) = N_c \exp\left[-\frac{E_g - \Delta\mu - \phi(x, U) - eU}{kT}\right] \quad (4)$$

$$p(x, U) = N_v \exp\left[-\frac{\Delta\mu + \phi(x, U)}{kT}\right] \quad (5) \quad I = Ae \int_0^W U(x, V) dx \quad (6)$$

$$\phi(x, U) = (\phi_o - eU) \left(1 - \frac{x}{W}\right)^2 \quad (7)$$

- (1) - Generation-recombination rate in the depleted layer
- (2), (3) -  $n_i$  and  $p_i$  are numerically equal to the equilibrium concentrations of electrons and holes, provided that the Fermi level coincides with recombination center level.
- (4), (5) -  $n(x, U)$  and  $p(x, U)$  are the concentrations of free carriers in the conduction and valence bands, respectively,  $n_o$  and  $p_o$  are their equilibrium values,  $\tau_{no}$  and  $\tau_{po}$  are effective lifetimes of electrons and holes, respectively, in the depleted region.
- (6) - Generation-recombination current density
- (7) - The potential energy in the depleted region  $W$ . The effective masses of electrons and holes are  $0.11m$  and  $0.63m$ , respectively ( $m_o$  is the mass of an electron in vacuum), carrier lifetimes in the depletion region of the barrier:  
 $\tau_{no} = \tau_{po} \approx 0.3 \times 10^{-9} \text{ s}$ .  
 The depth of the deep level is taken equal to  $E_t \approx 0.75 \text{ eV}$ .

## CONCLUSIONS

$\text{Cd}_{1-x}\text{Mn}_x\text{TeSe}$  single crystals were grown by the Bridgman method. According to the DTA data, the melting of the  $\text{Cd}_{0.96}\text{Mn}_{0.04}\text{Te}_{0.96}\text{Se}_{0.04}$  alloy occurs in the temperature interval of 1363-1378 K. This temperature interval is close to that found for pure CdTe. Superheating above the critical temperature of 1378 K by 25 K was applied to ensure full homogenization of the melt. The band gap of single crystals was found to be  $E_g = 1.495 \text{ eV}$ , and the resistivity of single crystals was  $\rho \approx 4 \cdot 10^2 \text{ Ohm-cm}$  at  $T = 293 \text{ K}$ . The Al/CMTS/Au structure had a pronounced diode characteristic and a rectification factor of  $K \approx 10^4$  at room temperature. The barrier height, formed during the vacuum deposition of Al on the p- $\text{Cd}_{1-x}\text{Mn}_x\text{TeSe}$  surface, was at least 0.9 eV. The generation-recombination charge transfer mechanism seems to be dominant in the Al/CMTS/Au diodes within the depleted region. The I-V curves of the diodes were quantitatively described in terms of the generation-recombination model of Saah-Noys-Shockley.